Patent 7,085,616 PATENT IN UNITED STATES PATENT AND TRADEMARK OFFICE

Patent No.: 7.085.616 Docket No: 5017/ISM/CORE/MCVD/SB

Issue Date: August 1, 2006 Patentee: Chin, et al.

Title ATOMIC LAYER DEPOSITION APPARATUS

REQUEST FOR CERTIFICATION OF CORRECTION

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

It is requested that a Certificate of Correction be issued correcting printing errors appearing in the above-identified United States patent. A copy of the text of the Certificate in the suggested form is enclosed.

As the error is that of the Patent Office, it is believed that no fee is due. However, the Commissioner is authorized to charge any additional fees that may be due to Deposit Account No. 20-0782.

Issuance of the Certificate of Correction would neither expand nor contract the scope of the claims as properly allowed, and re-examination is not required.

Respectfully submitted,

Mar 8,2057

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Approved for use through 01/31/2040, (MM 695-14)

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UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT N	O : 7,085,616
DATED	: August 1, 2006
INVENTOR	(S) : Chin et al.
	It is certified that errors appears in the above-identified patent and that said Letters Patent y corrected as shown below:
1	n column 3, line 21, delete "processing such" and insert processing-such, therefor.
; ; ;	in column 3, line 60, below "pulsed flow." insert Thereafter as indicated in step 370 of FIG 3, alternating monolayers of each deposition gas are chemisorbed onto the surface of the semiconductor wafer to form a material layer having a desired thickness thereon. Each monolayer is chemisorbed onto the surface of the semiconductor wafer as the wafer support is alternately moved between the two or more deposition regions through aperture 250, a an ew paragraph.
	in column 4, line 10, in Claim 1, delete "a deposition" and insert a vacuum deposition, therefor.
1	n column 4, line 14, in Claim 1, after "support is" insert vertically
1	n column 4, line 20, in Claim 3, delete "controls" and insert control, therefor.
I	n column 5, line 38, in Claim 15, after "support" delete "on" and insert to, therefor.

MAILING ADDRESS OF SENDER:

PATENT NO	7,085,616
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